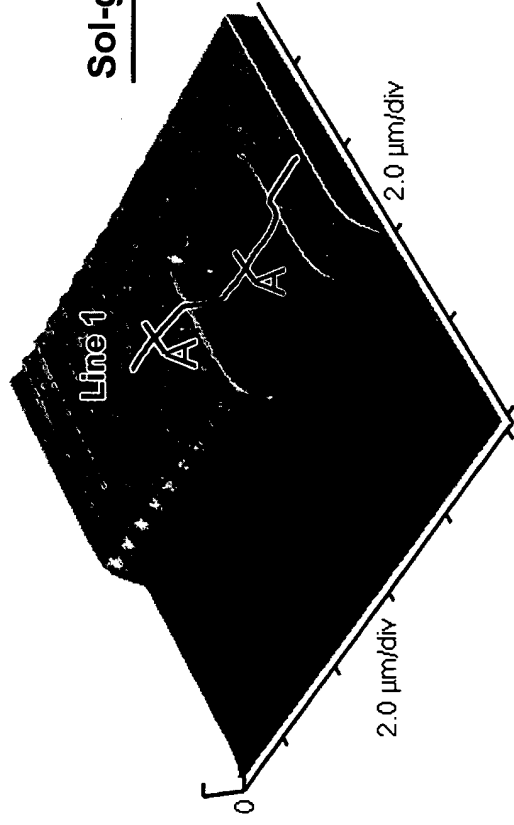


Repaired Programmed Mask Defects via DPN Using sol-gel based material

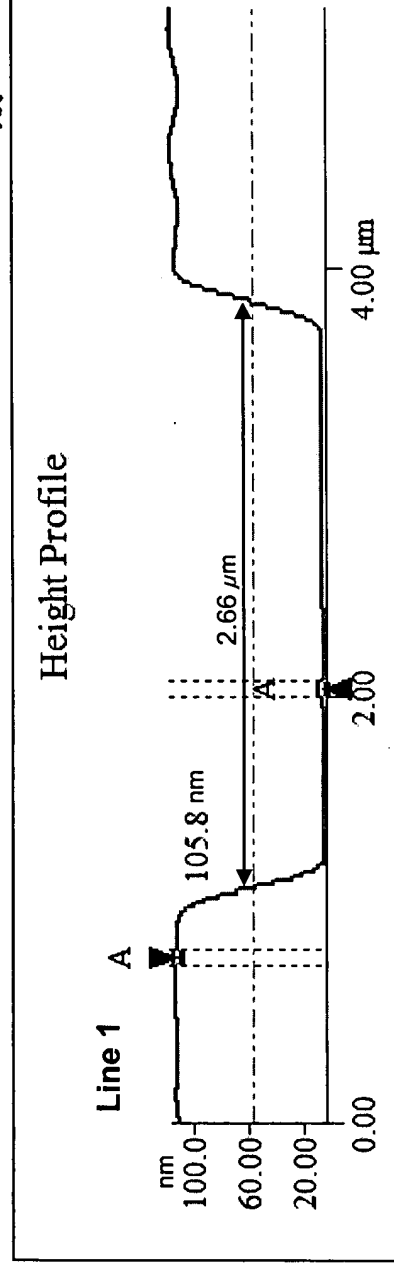
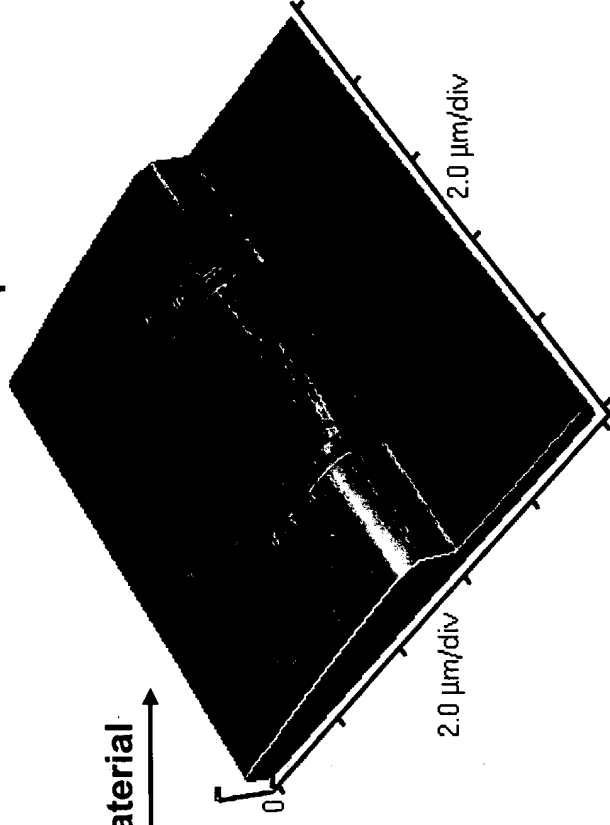


Defect before repair



Sol-gel based material

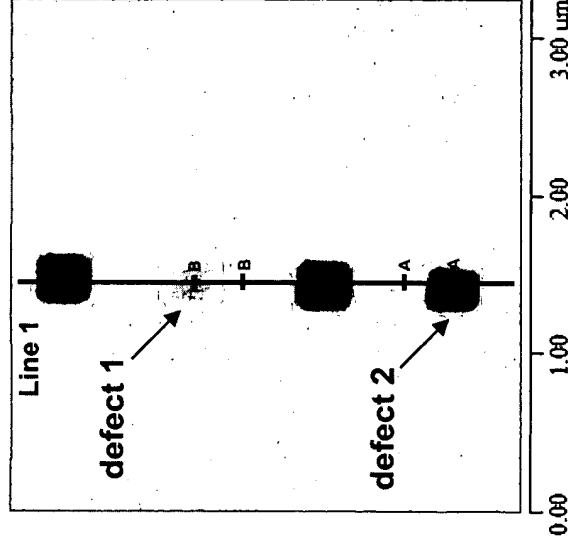
Defect after repair



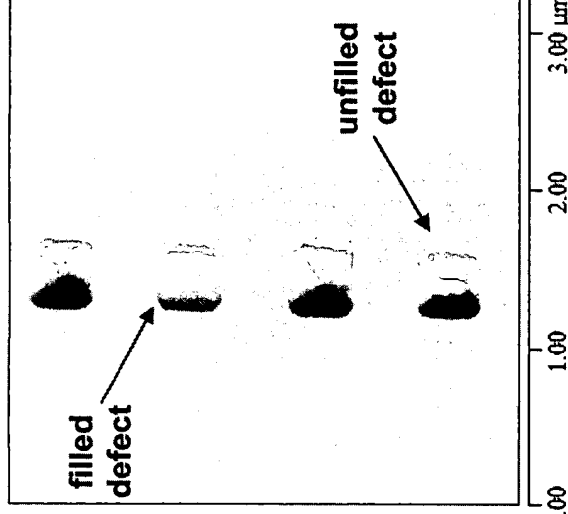
- 2.5 μm square defects with an open edge was repaired using fused silica Sol Gel material

Repaired Programmed Mask Defects via DPN Using sol-gel based material

AFM topographic image



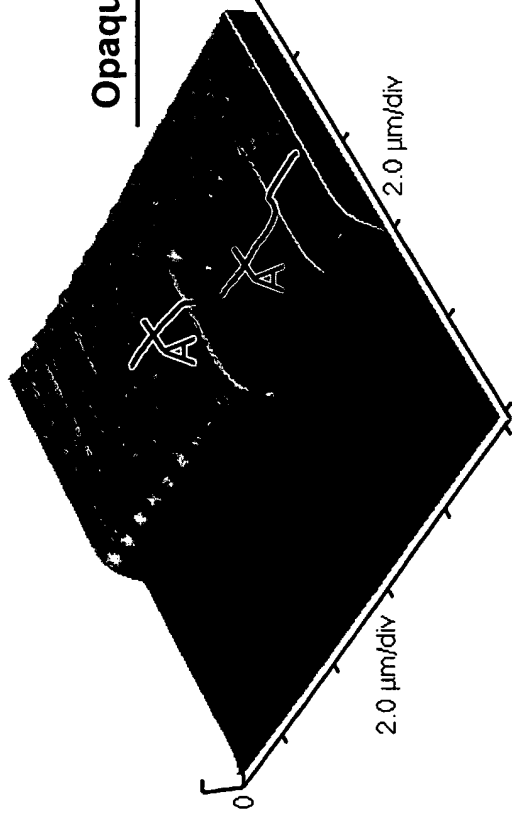
AFM error image



- Arrow points to the filled defect # 1 and unfilled defect # 2
- Selective deposition was achieved
- Height measurements are shown in the cursor profile after thermal curing
The material deposited in defect # 1 is approximately 135 nm (the height difference between filled and unfilled defect)
- Error image shows clearly the difference between filled and unfilled defects. The unfilled defects resemble the AFM tip geometry since the bottom of the defect can't be reached

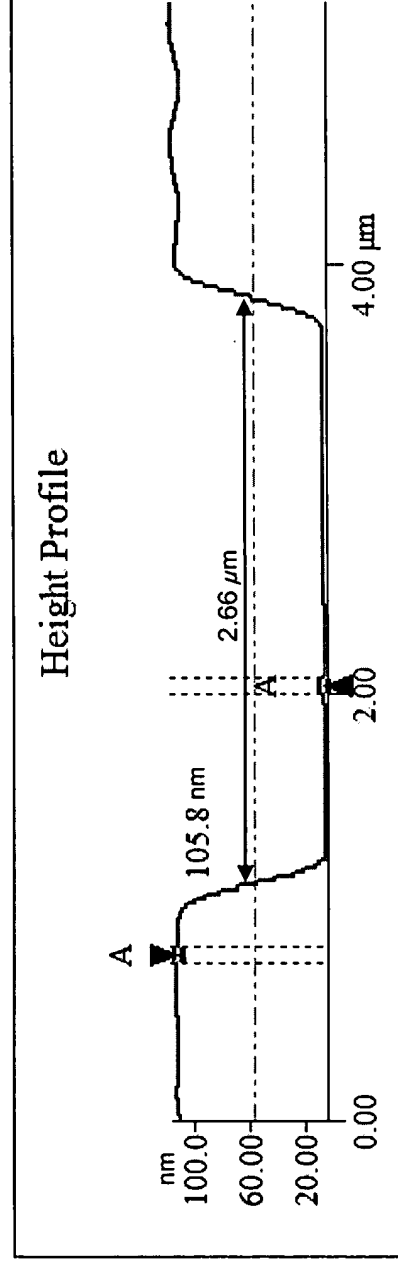
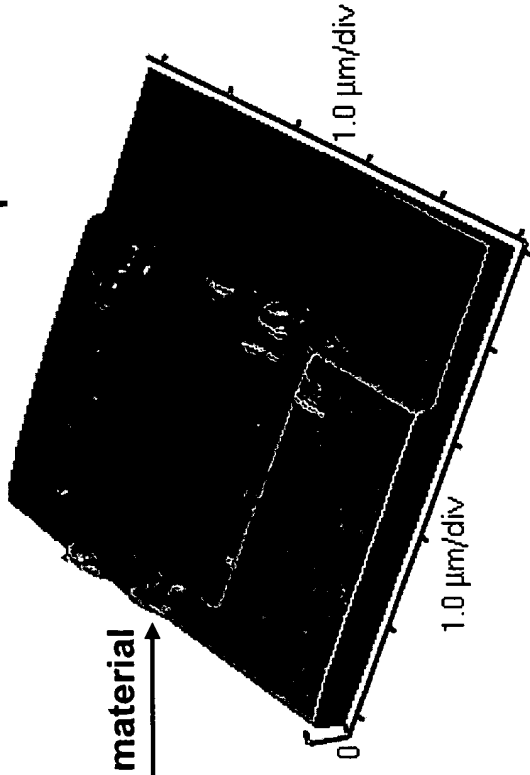
Repaired Programmed Mask Defects via DPN using Opaque Based Material

Defect before repair



Opaque based material

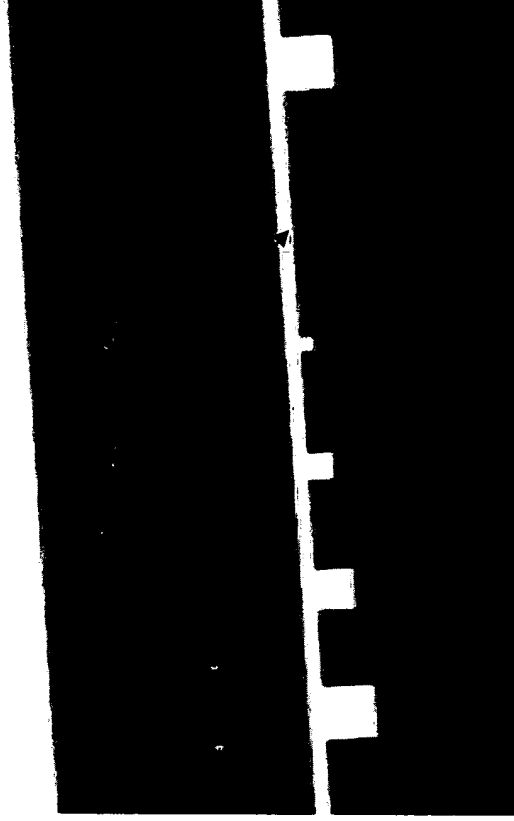
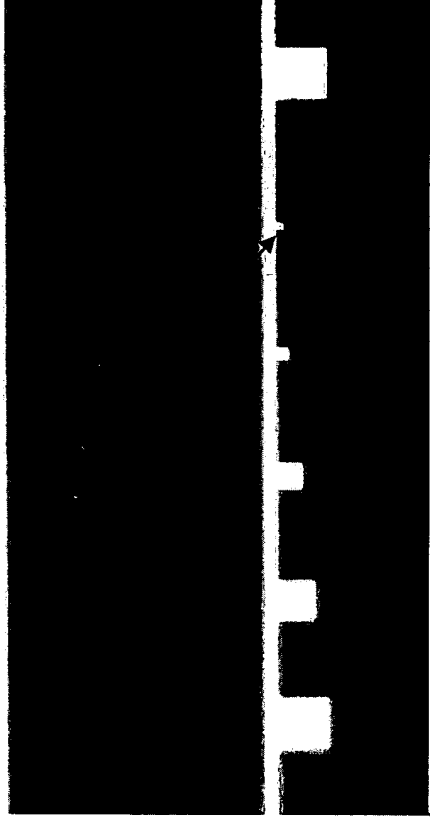
Defect after repair



- 2.5 μm square defects with an open edge was repaired opaque material

Repaired Programmed Mask Defects via DPN using Opaque Based Material

Optical images of a defect mask





NanoInk® and SII NanoTechnology (SIINT) Announce an Exclusive Licensing & Co-Development Agreement for Photomask Repair

(SKOKIE, Illinois – June 22, 2006) NanoInk, Inc. and SII NanoTechnology Inc. (SIINT), a subsidiary of Seiko Instruments Inc., today announced that they have signed an exclusive licensing agreement to provide nanoscale repair solutions to the photomask industry. The two companies will collaborate on projects that will involve modification of NanoInk's proprietary Dip Pen Nanolithography™ (DPN®) technology to be integrated with SIINT's photomask repair instruments and nanomachining platforms. Financial terms of the agreement were not disclosed.

Photomask repair industry challenges are tied to smaller defects that cannot be addressed with current options. Both companies anticipate that with computer chip nodes going down in size to 65nm and 45nm, the photomask repair industry requires capabilities that are available only with new technology provided by NanoInk's DPN.

The development work will be performed both in the United States of America and Japan. With an estimated 65% of photomask customers based in Asia, NanoInk believes that SIINT is the best partner to offer an excellent sales and marketing infrastructure to service this demanding market.

"This agreement offers SIINT the opportunity to work closely with a cutting edge US-based nanotechnology company that has a solid global intellectual property portfolio," said Dr. Hiroyuki Funamoto, President and Chief Executive Officer of SIINT. "With this co-development partnership, SIINT will bring innovative nanoscale repair solutions to the marketplace in the near future."

"I am thrilled that SIINT has decided to partner with NanoInk to design and manufacture a platform that can integrate repair capabilities," said Dr. Cedric Loiret-Bernal, Chief Executive Officer and President, NanoInk, Inc. "We believe that this agreement will allow the introduction of our unique DPN technology to global customers while raising standards for repair within the photomask industry."

About NanoInk®
NanoInk, Inc. is an emerging growth technology company specializing in nanometer-scale manufacturing and applications development for the life science and semiconductor industries. With DPN®, a patented and proprietary

nanofabrication technology that allows for unmatched flexibility, accuracy and also its high-resolution Nanoencryption™ technology, NanoInk is able to offer its pharmaceutical customers innovative solutions to fight counterfeiting and illegal diversion of blockbuster pharmaceutical products. Other key applications include nanoscale additive repair, and nanoscale rapid prototyping. Located in the new Illinois Science + Technology Park, north of Chicago, NanoInk currently has over 100 issued or pending patents and patent applications filed worldwide and has licensing agreements with Northwestern University, Stanford University, and the University of Illinois at Urbana-Champaign. For more information on products and services offered by NanoInk, Inc., see www.nanoink.net.

About SII NanoTechnology

SII NanoTechnology Inc. (SIINT), a subsidiary of Seiko Instruments Inc. (SII), is a leading company in the development of advanced, leading edge measurement and analysis instruments. Its head office is located in Tokyo, Japan. It was the first Japanese company to produce SMP and Focused Ion Beam (FIB) Systems. The company's products line-up also includes XRF Analyzers, XRF Coating Thickness Gauges, Thermal Analysis Systems, ICP-OES, ICP-MS and Mask Repair Systems. Many of these products are utilized to support leading edge research and development. Additional information about the company is available on the Internet at <http://www.siint.com/en/>.